

Hai Deng

List of Publications by Year in descending order

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papers

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1478505

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#	ARTICLE	IF	CITATIONS
1	Synthesis of a Fluoromethacrylate Hydroxystyrene Block Copolymer Capable of Rapidly Forming Sub-5 nm Domains at Low Temperatures. <i>ACS Macro Letters</i> , 2019, 8, 368-373.	4.8	43
2	Fast self-assembly of polystyrene- <i>b</i> -poly(fluoro methacrylate) into sub-5 nm microdomains for nanopatterning applications. <i>Journal of Materials Chemistry C</i> , 2019, 7, 2535-2540.	5.5	31
3	Methacrylic Block Copolymers Containing Liquid Crystalline and Fluorinated Side Chains Capable of Fast Formation of 4 nm Domains. <i>Macromolecules</i> , 2020, 53, 8757-8764.	4.8	11
4	Poly(2-vinylpyridine)- <i>b</i> -poly(fluorinated methacrylate) Block Copolymers Forming 5 nm Domains Containing Metallocene. <i>ACS Applied Polymer Materials</i> , 2020, 2, 3601-3611.	4.4	11
5	Synthesis of Liquid Crystalline Block Copolymers Self-assembled into Sub-5 nm Microdomains. <i>Journal of Photopolymer Science and Technology</i> = [Fotoporima Konwakai Shi], 2019, 32, 413-416.	0.3	8
6	Effects of composition on the properties of dual physically cross-linked hydrogel composed of polyvinyl alcohol and poly (acrylamide-co-acrylic acid). <i>Journal of Polymer Research</i> , 2017, 24, 1.	2.4	7
7	Ultra-Fast Block Copolymers for Sub-5 nm Lithographic Patterning. <i>Journal of Photopolymer Science and Technology</i> = [Fotoporima Konwakai Shi], 2018, 31, 483-486.	0.3	5
8	High Etch Resistant Ferrocene-Containing Block Copolymers with 5 nm Patterning Capability. <i>Journal of Photopolymer Science and Technology</i> = [Fotoporima Konwakai Shi], 2020, 33, 537-540.	0.3	4
9	Highly Ordered Methacrylate Block Copolymers Containing Liquid Crystal Side Chains. <i>Journal of Photopolymer Science and Technology</i> = [Fotoporima Konwakai Shi], 2020, 33, 541-544.	0.3	2
10	Synthesis of Fluorine-containing Polyacrylamide Block Copolymer and Their Application for Rapidly Formation of Sub-10 nm Microdomains. <i>Journal of Photopolymer Science and Technology</i> = [Fotoporima Konwakai Shi], 2019, 32, 389-393.	0.3	1
11	Development of 90 NM & 5 NM High Resolution Advanced Lithographic Patterning Materials. , 2020, , .		0
12	Synthesis of Highly Ordered Fluorinated Copolymers with One Polyhydroxystyrene Block for Subsequent Metal Incorporation. <i>Journal of Photopolymer Science and Technology</i> = [Fotoporima Konwakai Shi], 2021, 34, 339-343.	0.3	0
13	Synthesis of Highly Ordered Si-Containing Fluorinated Block Copolymers. <i>Journal of Photopolymer Science and Technology</i> = [Fotoporima Konwakai Shi], 2021, 34, 329-334.	0.3	0
14	Synthesis of Ordered Fluorinated BCPs with One Block Composed of Random Copolymer. <i>Journal of Photopolymer Science and Technology</i> = [Fotoporima Konwakai Shi], 2021, 34, 335-338.	0.3	0